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(54) **SYSTEM AND METHOD FOR CVD FILM
DEPOSITION**

an RF power source 15 connected to the matching
box.

(57) Abstract:

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PROBLEM TO BE SOLVED: To provide a system and a method for CVD film deposition, in which a fixed cost is reduced and the thickness fluctuation of the thin film deposited on the inside of a container can be reduced.

SOLUTION: The CVD film deposition system is a system for depositing DLC(diamond-like carbon) film on the respective insides of a plurality of PET (polyethylene terephthalate) bottles 7a to 7d. This system has: 1st to 4th external electrodes 3a to 3d arranged in a manner to enclose the respective outsides of the PET bottles; 1st to 4th internal electrodes 9a to 9d arranged inside the PET bottles, respectively; a gas-introducing means for introducing source gas into the respective insides of the PET bottles; 1st to 4th variable condensers 21a to 21d connected to the 1st to 4th external electrodes 3a to 3d, respectively; a matching box 14 connected to the 1st to 4th variable condensers; and

